

EE 421 / ECG 621 Digital IC Design

OCT. 18, 2013

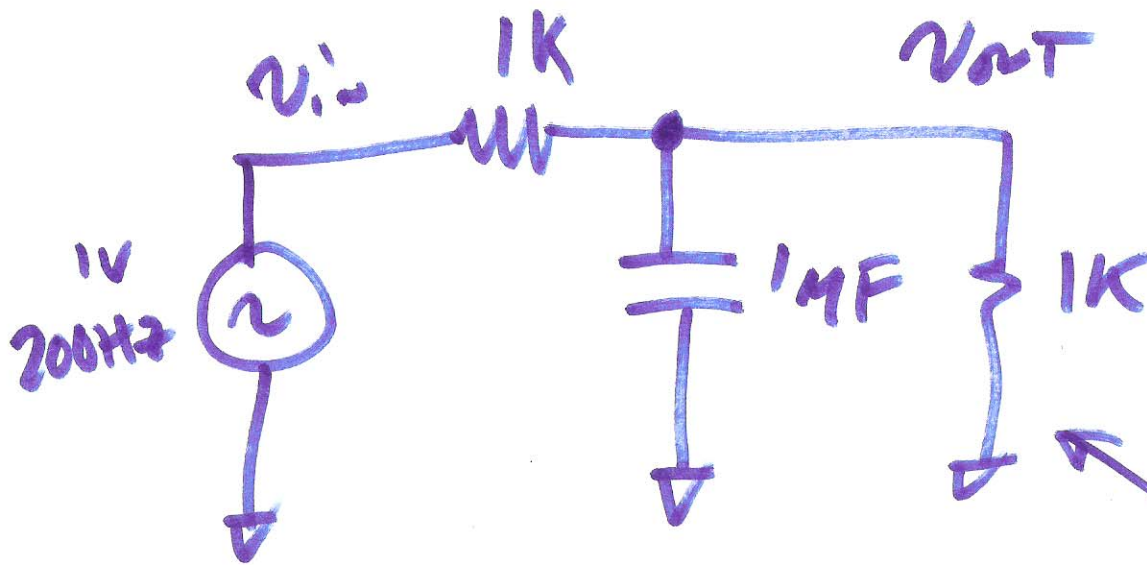
Lecture 16

Review for midterm

Chs. 1-6

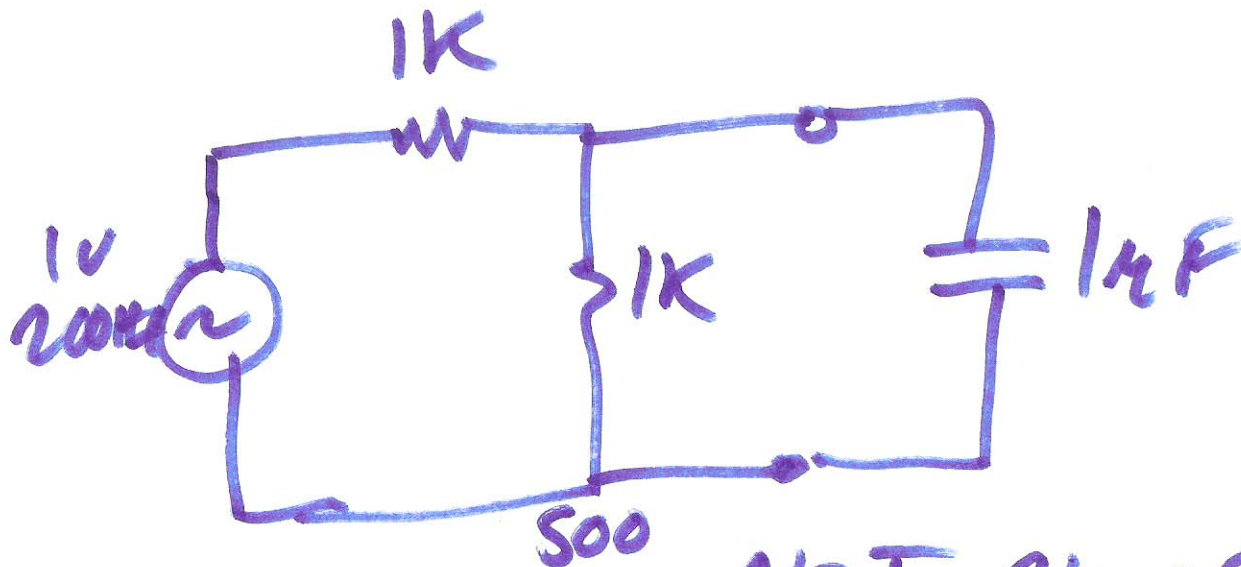
H.W. problems assigned
and end of
chapter

Quizzes

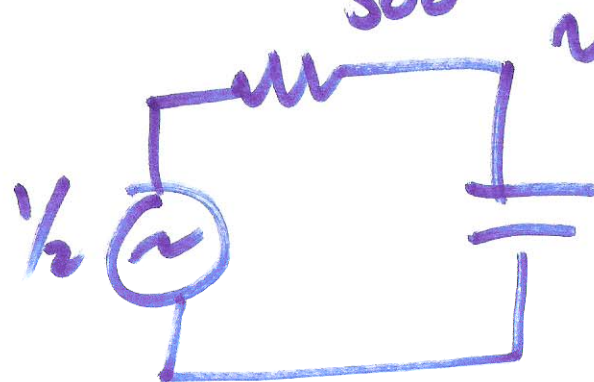


Sketch
 V_{out} & V_{in}
 on s-plane
 plot

$$Z = \frac{1K \cdot \frac{1}{j\omega 10^{-6}}}{1K + \frac{1}{j\omega 10^{-6}}}$$



$$= \frac{10^3}{1 + j\omega 10^{-3}}$$



$$V_{out} = V_{in} \cdot \frac{10^3}{1 + j\omega 10^{-3}}$$

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$$\frac{v_{out}}{v_{in}} = \frac{1 + j0}{2 + j\omega 10^{-3}} = \frac{1}{\sqrt{4 + (2\pi f \cdot 10^{-3})^2}}$$

$$\left| \frac{v_{out}}{v_{in}} \right| = \frac{\sqrt{1^2 + 0^2}}{\sqrt{2^2 + (2\pi f 10^{-3})^2}} = \frac{1}{2} \frac{1}{\sqrt{1 + (2\pi f \cdot 10^{-3})^2}}$$

$$\angle \frac{v_{out}}{v_{in}} = \tan^{-1} \frac{0}{1} - \tan^{-1} \frac{2\pi f \cdot 10^{-3}}{2}$$

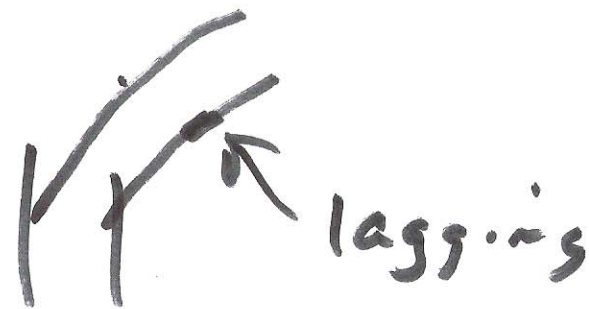
$$4 = (2\pi f_{3dB} \cdot 10^{-3})^2$$

$$2 = 2\pi f_{3dB} \cdot 10^{-3}$$

$$f_{3dB} = \frac{1 \text{ kHz}}{\pi} = 159 \text{ Hz}$$

$$\left| \frac{v_{out}}{v_{in}} \right| = \frac{1}{\sqrt{2^2 + (2\pi \cdot 200 \cdot 10^{-3})^2}}$$

$$\begin{aligned} \angle \tan^{-1} &= -\tan^{-1} \pi \cdot 200 \cdot 10^{-3} \\ &= -\tan^{-1} \cdot 2 \cdot \pi \end{aligned}$$



$$\frac{\Delta t}{T} \cdot 2\pi = \tan^{-1} \cdot 2\pi$$

N-well $\rightarrow$ Resistor
diode with the p-sub
Body of PMOS

RC delay of a transmission
LINE

$\swarrow$ derive $0.35rc l^2$

depletion C $\swarrow$ bottom CMP
sidewall

reverse recovery time

Laying resistors in small areas

design rules

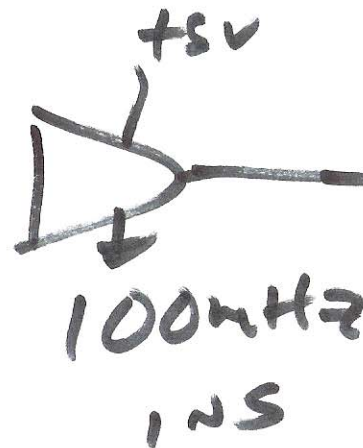
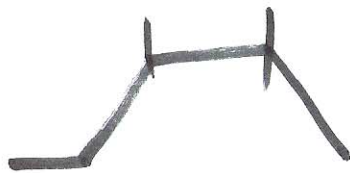
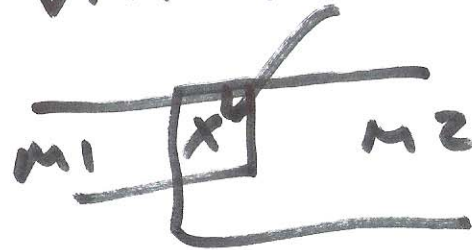
Energy band diagrams what sets N-well
spacing

Suppose you forward bias a diode
Sketch Energy band

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Metal layers

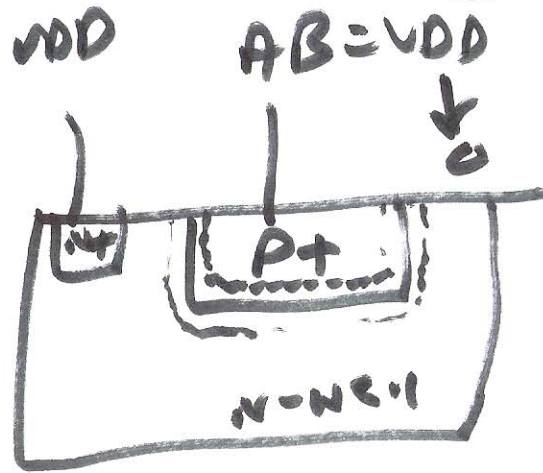
Layouts
electromigration
resistance of the line
parasitic cap.
via resistance



Estimate I_{peak}
AVG. power

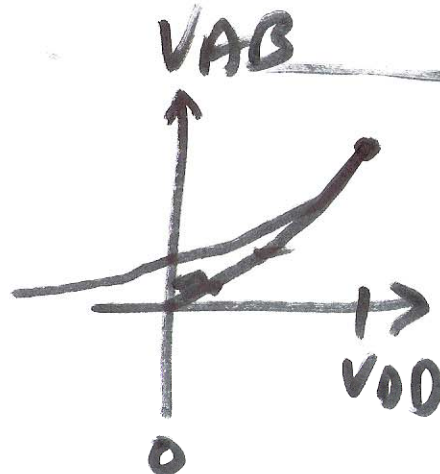
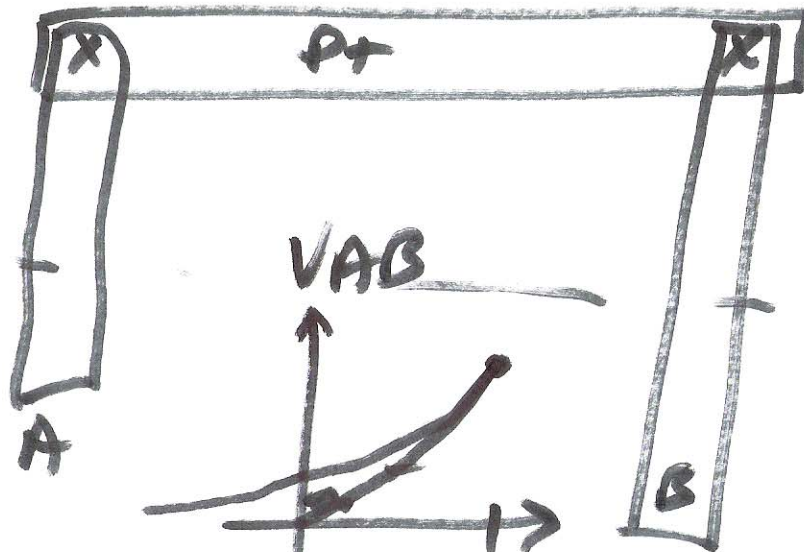
$$I = C \frac{dV}{dt} = \frac{5}{1ns} \cdot 10ps$$

CH. 34



ACTIVE AREA
PN junctions
Layouts
estimate R

$$R_{D,P+} = \frac{50\Omega}{\square}$$



Polysilicon

Describe what
polysilicon is

used to form a MOSFET
self-aligned gate
silicide

make with poly
poly1 - poly2

drawn width
length $\rightarrow$ L_{draw}

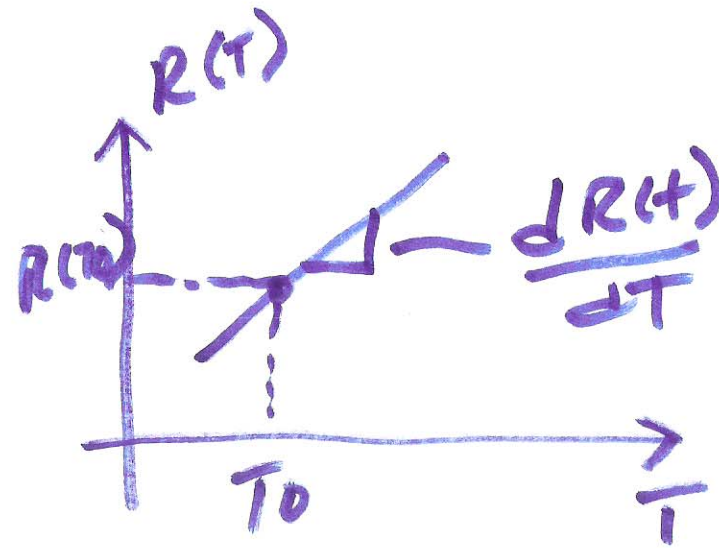
L_{eff}

L_{erc}

DIG
CLM

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Resistor temp co.



$$R(T) = R(T_0) + \frac{dR(T)}{dT} (T - T_0)$$

$$= R(T_0) \left(1 + \frac{1}{R(T_0)} \frac{dR(T)}{dT} (T - T_0) \right)$$

using unit elements
why?
How? why?

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MOSFETS

IV curves

Regions of operation
Strong, weak, Accumul.

Oxide cap.

MOSFET CAPS.

body effect Threshold voltage derivation
Subthreshold current Contact potentials
velocity saturation Threshold adjust
etc.

Know how to derive Q'_b , Q'_I , Q'_{CH}
square-law equations

C_{gs} derivation in saturation